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REDACTED

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TDG PATENT HARVESTING SESSION  
GROUP 2—ROOM C-2

Technical Leader: Chris Lyons

TOPIC: Advanced Patterning Modules

AMD INVENTION DISCLOSURE

TLD ID# REDACTED  
Sunnyvale x42110, return to MS68, Texas x55964 return to MS562

Project: ☐, Product: ☐, Process: ☐, Technology ☐, to which the invention applies (identify):

List 2 to 5 key words useful to search by to find patents or art related to this invention:

Working title of invention: Dual mask to change focus for printing small contacts  
or vias

INVENTOR/SESSION PARTICIPANT ADDRESS INFORMATION IS ON THE NEXT PAGE (1A)

Inventor's signature : \_\_\_\_\_ date : \_\_\_\_\_  
Inventor's printed full name: RS + all + U30.0 + Hung E. Kim Citizenship: \_\_\_\_\_  
Employee #: \_\_\_\_\_ Extension: \_\_\_\_\_ Mail stop: \_\_\_\_\_ Home telephone: ( ) \_\_\_\_\_  
Division: \_\_\_\_\_ Directorate: \_\_\_\_\_ Dept #: \_\_\_\_\_ Dept : \_\_\_\_\_ Manager: \_\_\_\_\_  
Residence address: \_\_\_\_\_  
Post Office address: \_\_\_\_\_

Co-Inventor's signature : \_\_\_\_\_ date : \_\_\_\_\_  
Co-Inventor's printed full name: \_\_\_\_\_ Citizenship: \_\_\_\_\_  
Employee #: \_\_\_\_\_ Extension: \_\_\_\_\_ Mail stop: \_\_\_\_\_ Home telephone: ( ) \_\_\_\_\_  
Division: \_\_\_\_\_ Directorate: \_\_\_\_\_ Dept #: \_\_\_\_\_ Dept : \_\_\_\_\_ Manager: \_\_\_\_\_  
Residence address: \_\_\_\_\_  
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Division: \_\_\_\_\_ Directorate: \_\_\_\_\_ Dept #: \_\_\_\_\_ Dept : \_\_\_\_\_ Manager: \_\_\_\_\_  
Residence address: \_\_\_\_\_  
Post Office address: \_\_\_\_\_

List on additional sheet if there are more co-inventors and list total number of inventors here: \_\_\_\_\_  
Name(s) of attorney(s) preferred by inventor(s) to prepare patent application, if known:

LAW FIRM: FOLEY & LARDNER  
ATTORNEYS: PHIL ARTICOLA and TOM BILODEAU

Witness 1 initial: \_\_\_\_\_ Witness 2 initial: \_\_\_\_\_

# AMD INVENTION DISCLOSURE

TLD ID# \_\_\_\_\_

Rec'd date \_\_\_\_\_

California x42110, return to MS68,

Texas x55964 return to MS562,

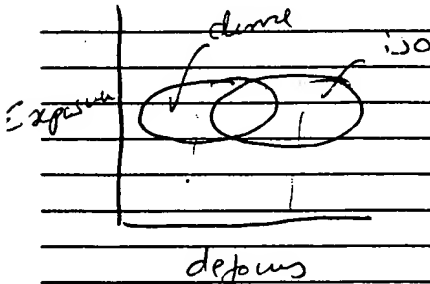
Dresden x83401 Silke Kretzschmar at MS E21-PP.

State the problem solved by this invention: \_\_\_\_\_

Brief description and/or sketch of invention (please attach copies of AMD patent notebook pages, reports or drawings): \_\_\_\_\_

As context size shrinks the experimental data shows that

The test for printing dense &amp; isolated vias are different

→ Proposal is to use 2 masks to print the  
2 types of vias separately with2 ~~types~~ different focus settings to get  
best process.

- Broader claim is as we have many pitches  
we may use many masks with different  
optical settings to get best process window  
↓  
include illuminator, focus, NA, Sigma etc.

Patent notebook # \_\_\_\_\_ Page numbers \_\_\_\_\_ Number of drawings \_\_\_\_\_

Witness 1 initial: \_\_\_\_\_ Witness 2 initial: \_\_\_\_\_